

STRUCTURED ANALOG CMOS DESIGN

Based on the Device Inversion Level

Danica Stefanovic

STATE OF THE ART

- No general analog design methodology.
- No general **design approach**.
- **CAD tools** for simulation, layout generation and post layout verification.
- Large number of **analog design automation** tools,
but only in the university domain!
- Few analog design automation tools in industry.

HOW TO

- Deal with increasing circuit **complexity** ?
- Deal with very **demanding specifications** sets ?
- Estimate **technology limits** ?
- Bridge the gap between **hand-calculations** and simulations ?
- Use the **device physics understanding** for analog design ?
- Optimize analog circuits and find the best **trade-offs** ?
- Develop CAD tools for **analog design assistance** ?
- **Encapsulate** analog design knowledge ?

THIS WORK

Analog design approach

- **Structured analog design**
- **Procedural design**

Transistor level design

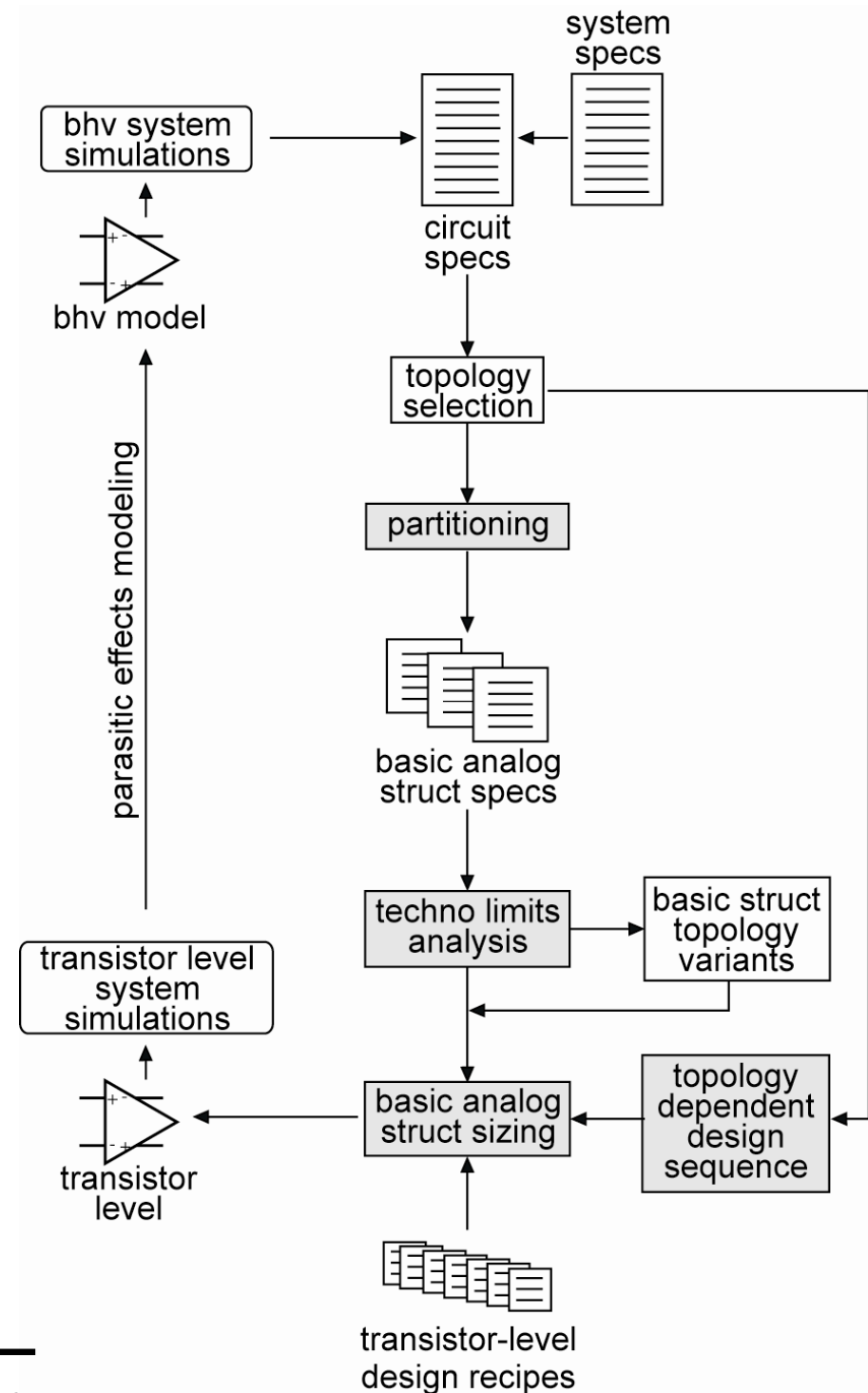
- **the device inversion level as a key variable**

CAD tool for analog design assistance

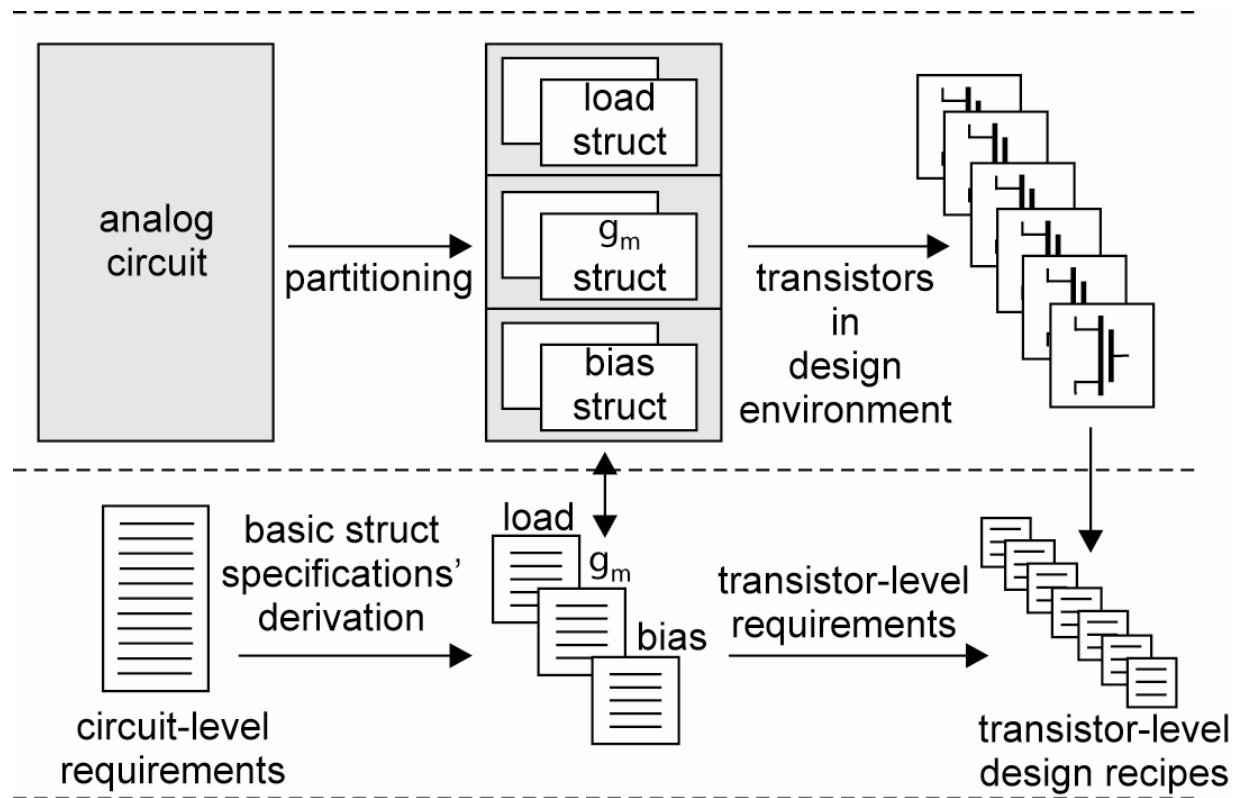
- **PAD tool**
- **BSIM2EKV converter**

BASIC CONCEPT

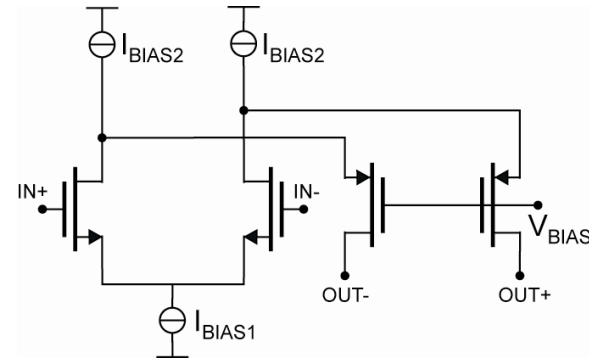
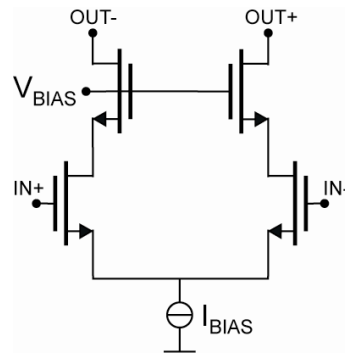
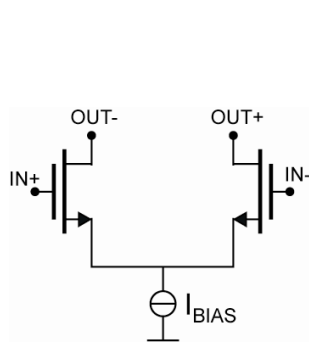
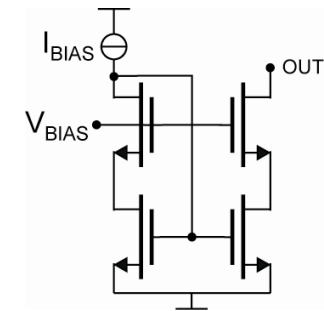
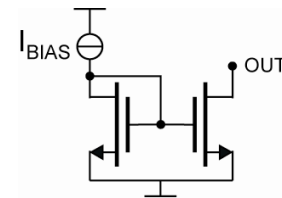
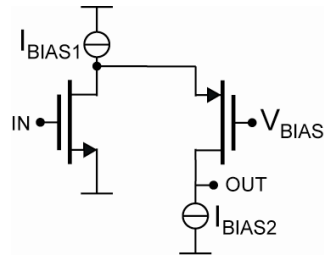
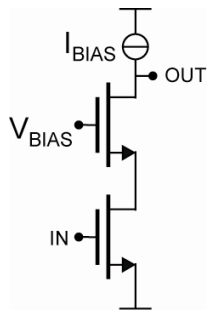
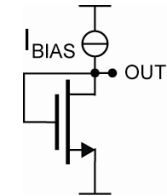
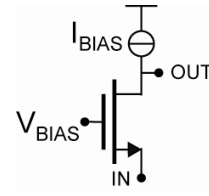
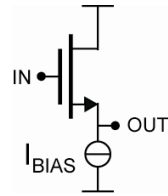
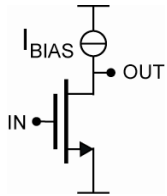
- **Circuit-level specifications from system-level simulations**
- **Basic analog structures library**
- **Procedural design scenarios**
- **Sizing and optimization on the level of basic analog structures**
- **Topology variants**



STRUCTURED ANALOG DESIGN



BASIC ANALOG STRUCTURES LIBRARY



BASIC ANALOG STRUCTURES LIBRARY

→ Classification

Transconductance structures:

CS, CD, CG, cascode, differential pair

Load structures:

simple and cascode current mirror

Bias structures:

simple and cascode current mirror

BASIC ANALOG STRUCTURES LIBRARY

→ **Design parameters**

Transconductance structures:

transconductance, input range, noise,
voltage mismatch (offset)
output resistance, output swing, parasitic capacitances

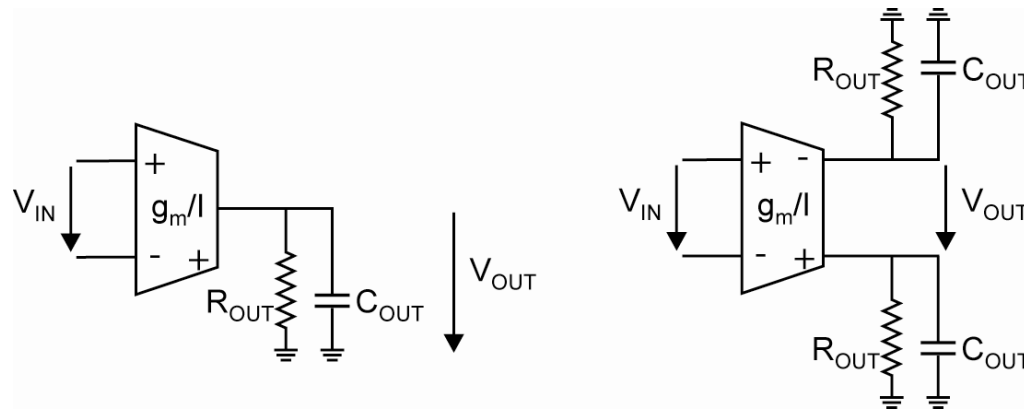
Load structures:

output resistance, saturation voltage,
parasitic capacitances, noise, current mismatch

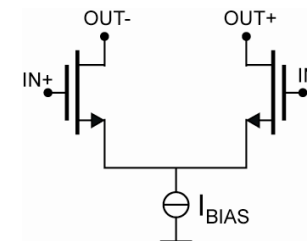
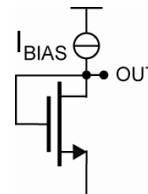
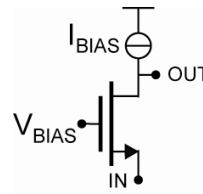
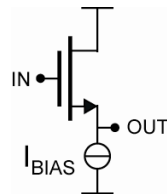
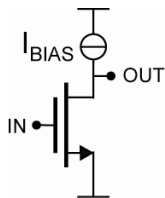
Bias structure:

output resistance, saturation voltage, current mismatch

BEHAVIORAL MODEL OF ANALOG CELL



TRANSISTOR DESIGN CASES



TRANSISTOR LEVEL DESIGN

→ **Good MOS model**

- Based on physical behavior
- Covers all significant physical effects
- Global, compact, accurate
- Covers all geometry ranges
- Correct I-V characteristics, correct current derivatives
- Accurate modeling of the intrinsic capacitances
- Simple and fast extraction procedure
- Easy implementation, no convergence problems

TRANSISTOR LEVEL DESIGN

→ **MOS model dedicated to analog design**

→ **Small number of parameters** with physical meaning

→ **Hierarchical structure**

→ Model equations **approximations** without a great loss of accuracy

→ Accurate modeling of **weak and moderate inversion** behavior

→ **Continuous expressions** of current derivatives

→ **EKV MOS model** → **its basic concept makes it possible to develop a design approach at the transistor level**
(<http://legwww.epfl.ch/ekv/>)

TRANSISTOR LEVEL DESIGN

→ Design parameters vs. design variables

saturation voltage V_{DSsat}

transconductance g_m

output conductance g_{DS}

parasitic capacitances

intrinsic gain A_i

transition frequency f_t

equivalent noise

saturation current I_{Dsat}

inversion factor IF

transistor width W

transistor length L

ratio W/L

area WL

TRANSISTOR LEVEL DESIGN

→ **Design variables**

$$I_{pol} = I_{Dsat} = 2nKP\left(\frac{W}{L}\right)V_t^2 \cdot IF$$

$$\rightarrow \frac{W}{L} = \frac{I_{Dsat}}{2nKPV_t^2 \cdot IF}$$

$$\rightarrow W = \left(\frac{W}{L}\right) \cdot L = \frac{I_{Dsat}}{2nKPV_t^2 \cdot IF} \cdot L$$

$$\rightarrow WL = \left(\frac{W}{L}\right) \cdot L^2 = \frac{I_{Dsat}}{2nKPV_t^2 \cdot IF} \cdot L^2$$

inversion factor IF

transistor length L

TRANSISTOR LEVEL DESIGN

→ Design parameters

$$V_{DSSat} = V_t \cdot (2\sqrt{IF} + 4)$$

$$\frac{g_m}{I_{Dsat}} = \frac{1}{nV_t} \cdot \frac{1}{\frac{1}{2} + \sqrt{IF + \frac{1}{4}}}$$

$$g_{DS} = \frac{I_{Dsat}}{L \cdot V_a}$$

$$A_i = \left(\frac{g_m}{I_{Dsat}} \right) \cdot L \cdot V_a$$

$$(\Sigma C_i)_{MAX} = C_{ox} \cdot \frac{I_{Dsat}}{2nKV_t^2 \cdot IF} \cdot L^2$$

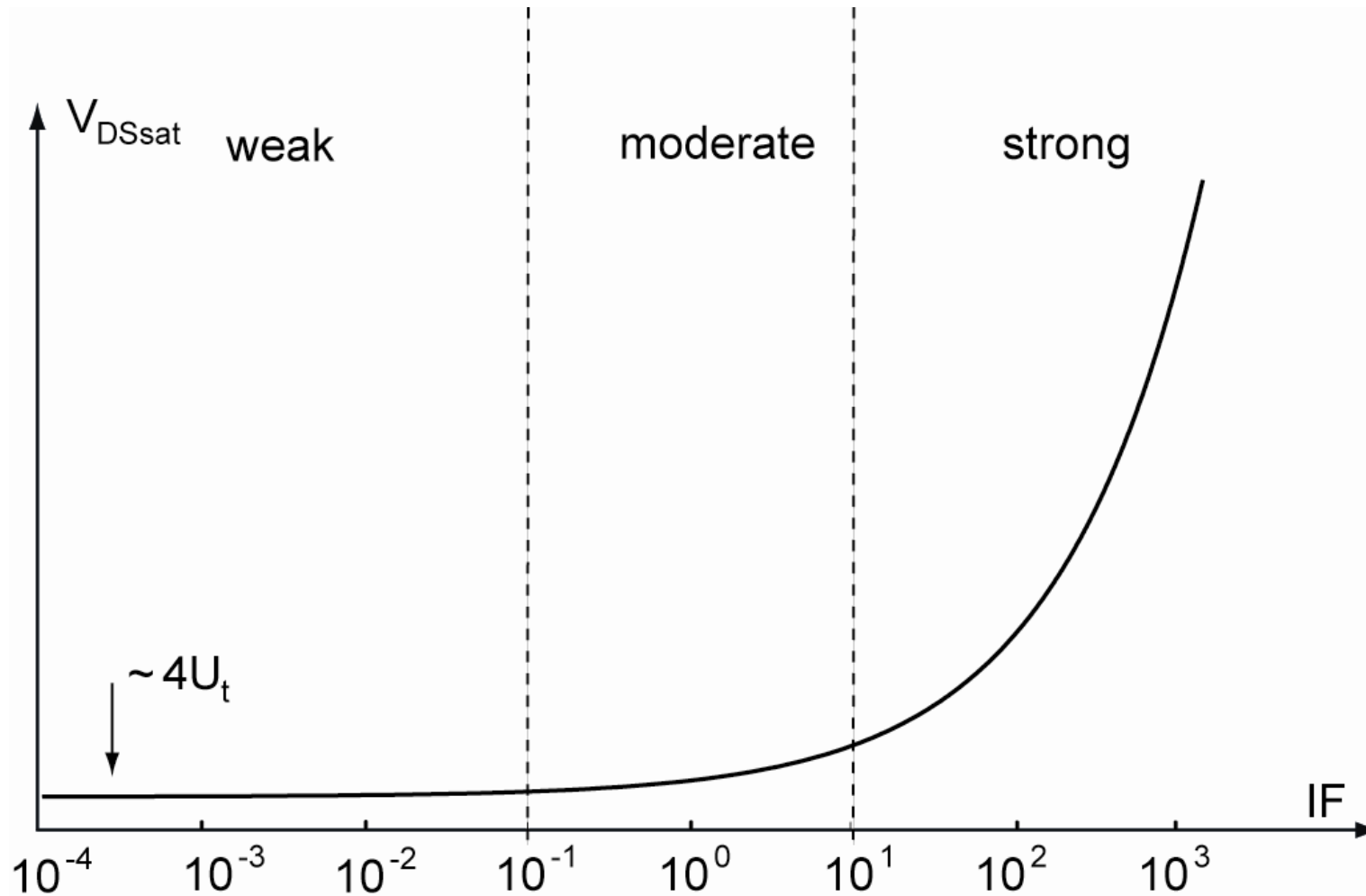
$$f_t = \frac{g_m}{2\pi(\Sigma C_i)_{MAX}} = \left(\frac{g_m}{I_{Dsat}} \right) \cdot \frac{nKV_t^2 \cdot IF}{\pi C_{ox} \cdot L^2}$$

$$V_{n,th}^2 = \frac{4KT \cdot n \cdot \frac{1}{1+IF} \cdot \left(\frac{1}{2} + \frac{2}{3}IF \right)}{\left(\frac{g_m}{I_{Dsat}} \right) \cdot I_{Dsat}}$$

$$V_{n,fl}^2 = \frac{2nKV_t^2 \cdot KF \cdot IF}{L^2 C_{ox} f^{AF} \cdot I_{Dsat}}$$

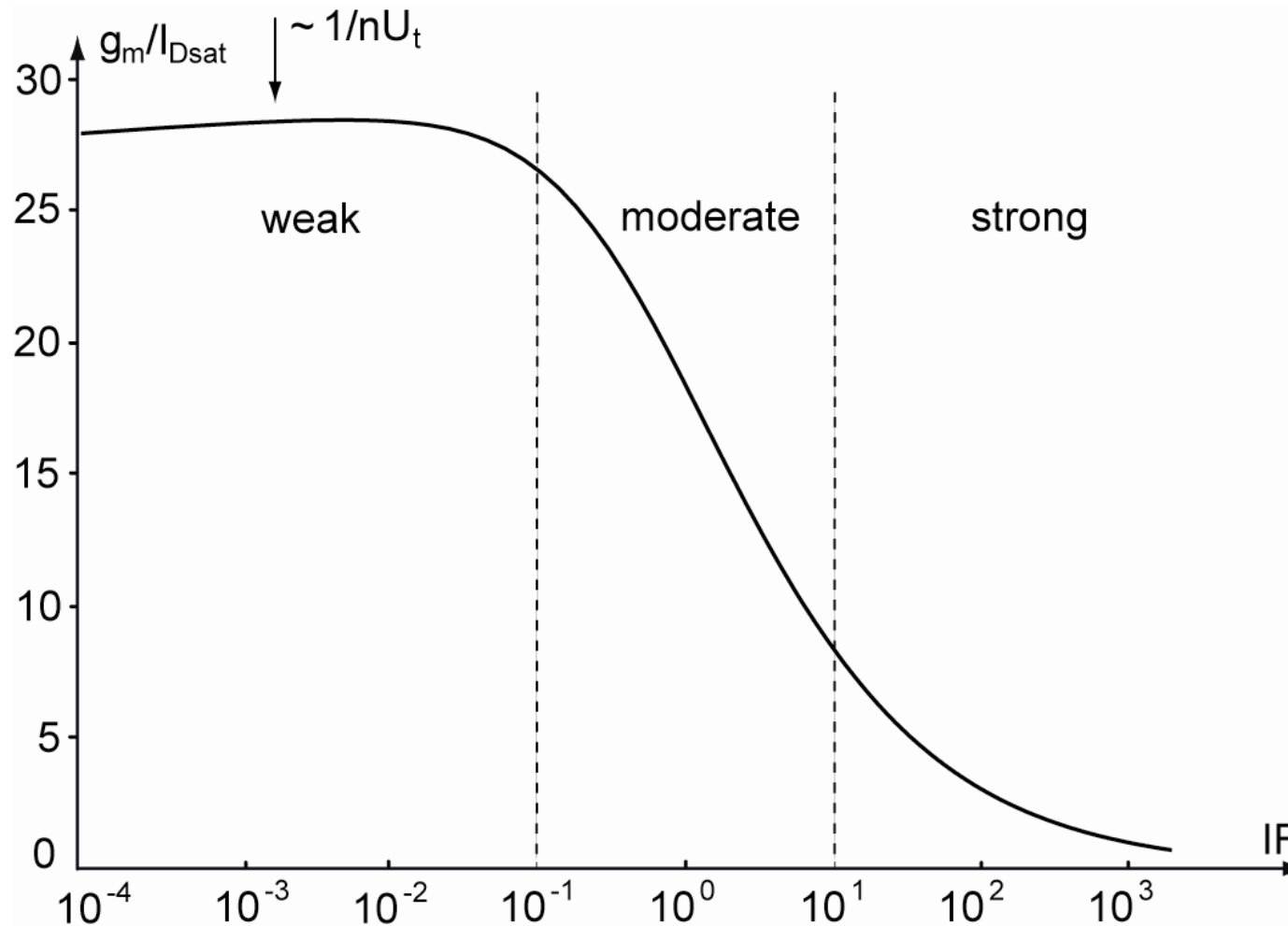
TRANSISTOR LEVEL DESIGN

→ Design parameters vs. variables



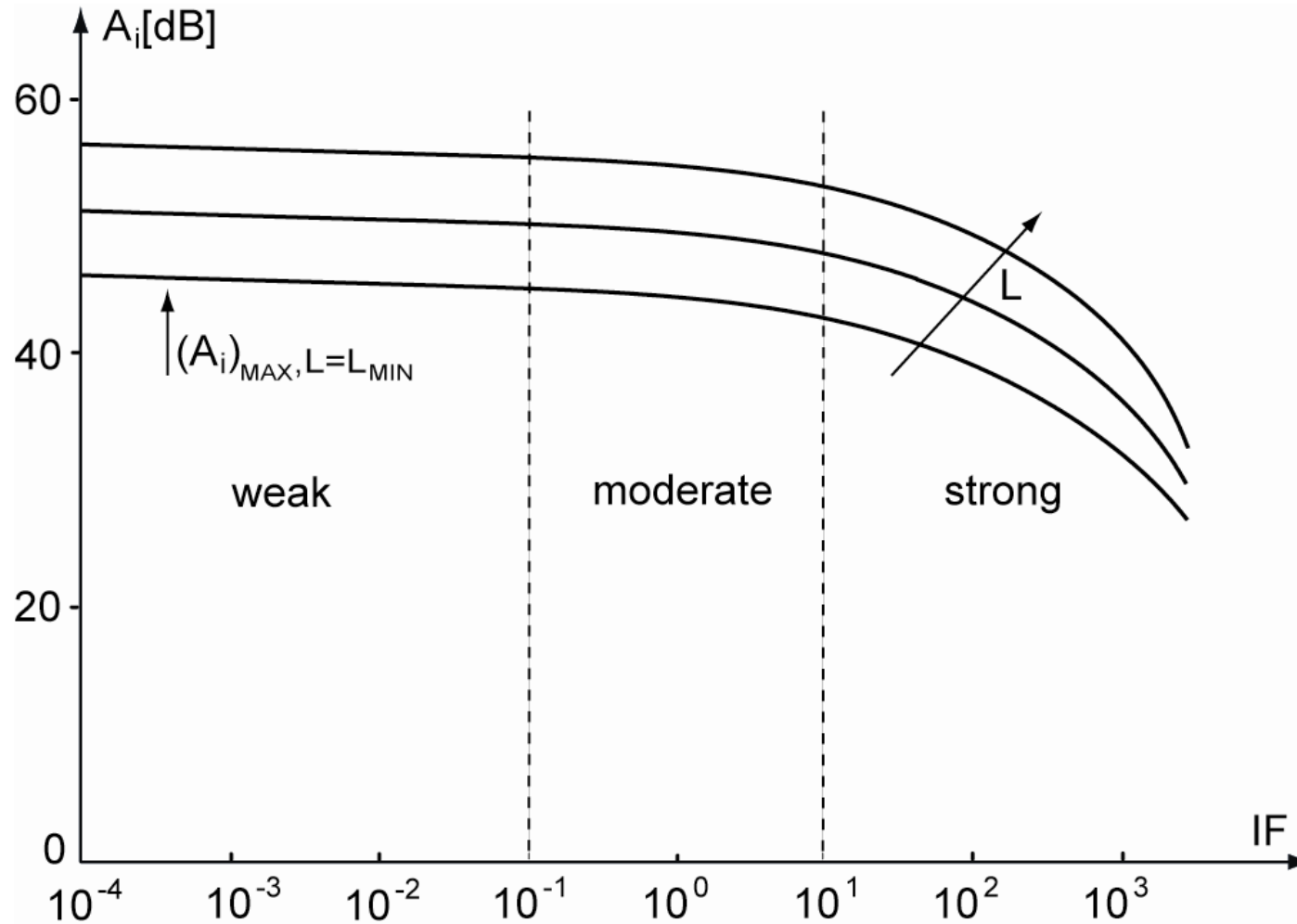
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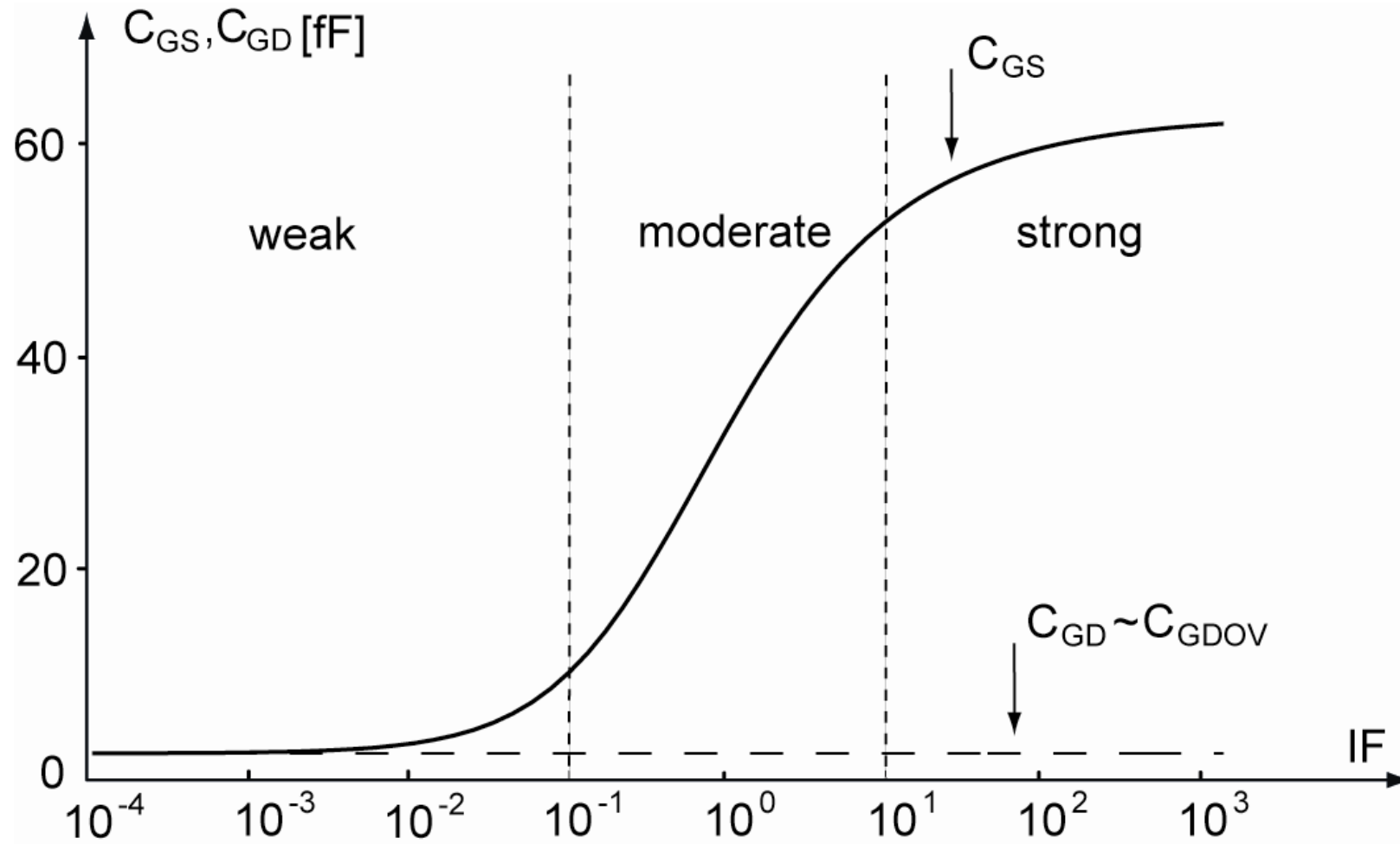
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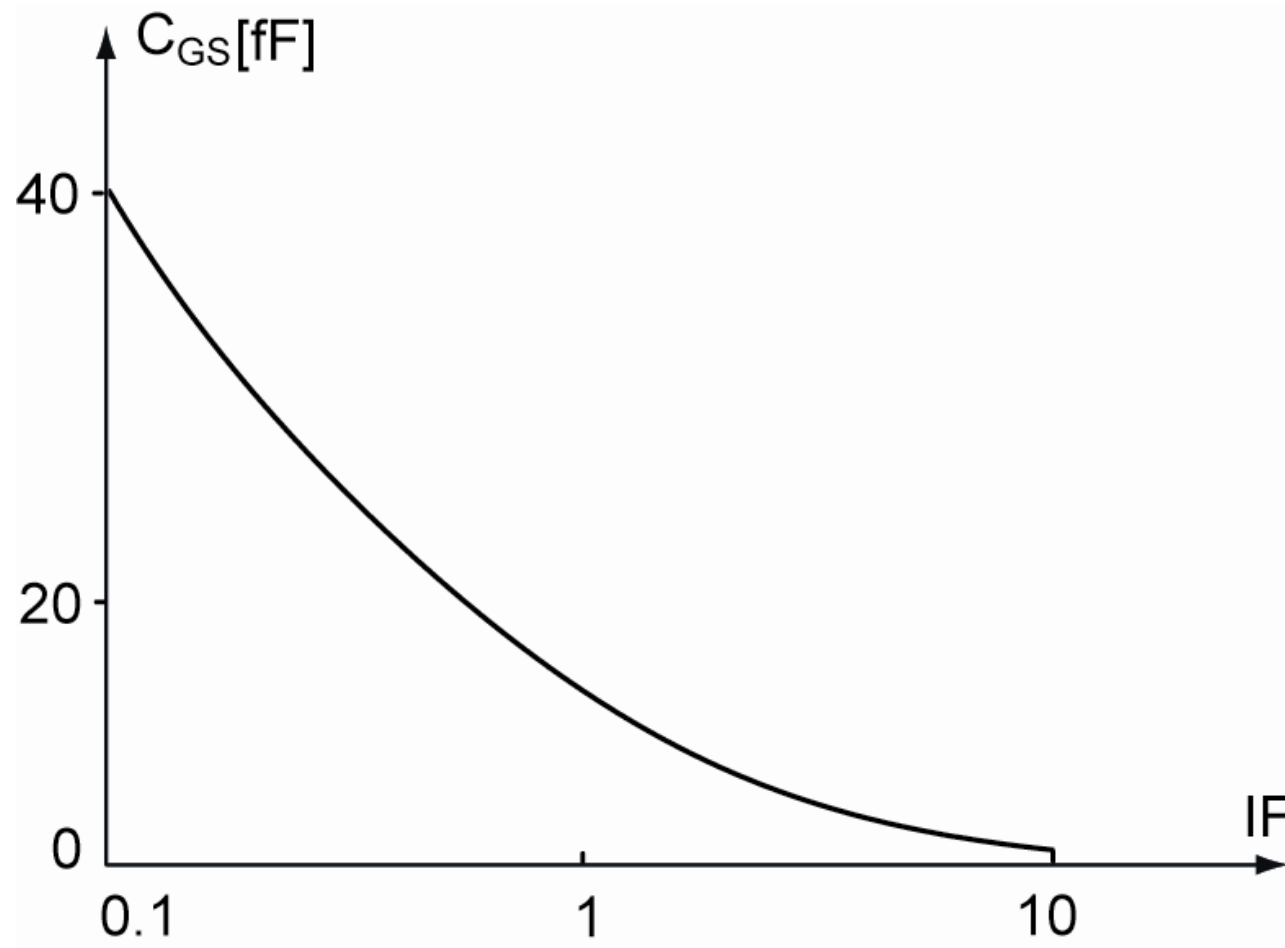
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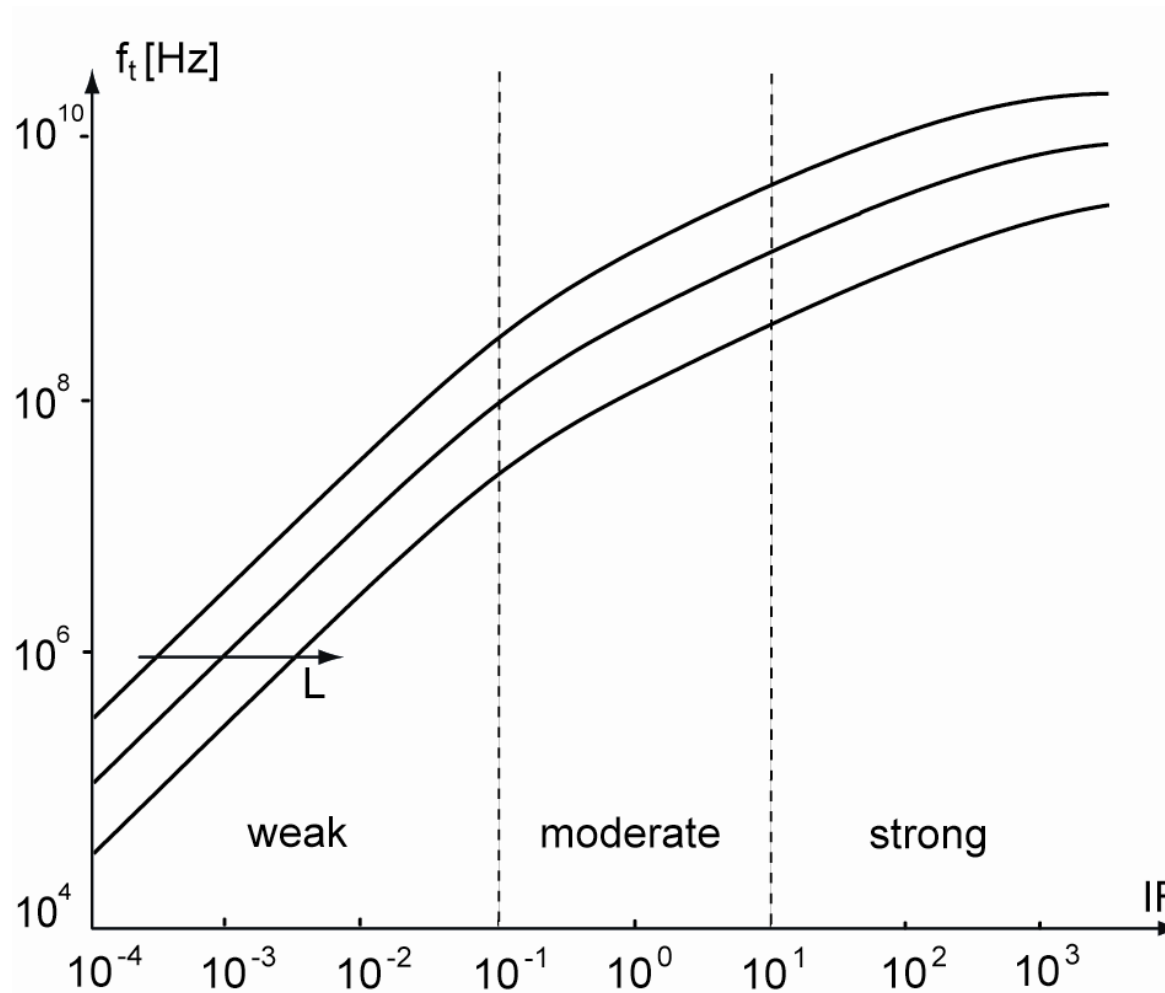
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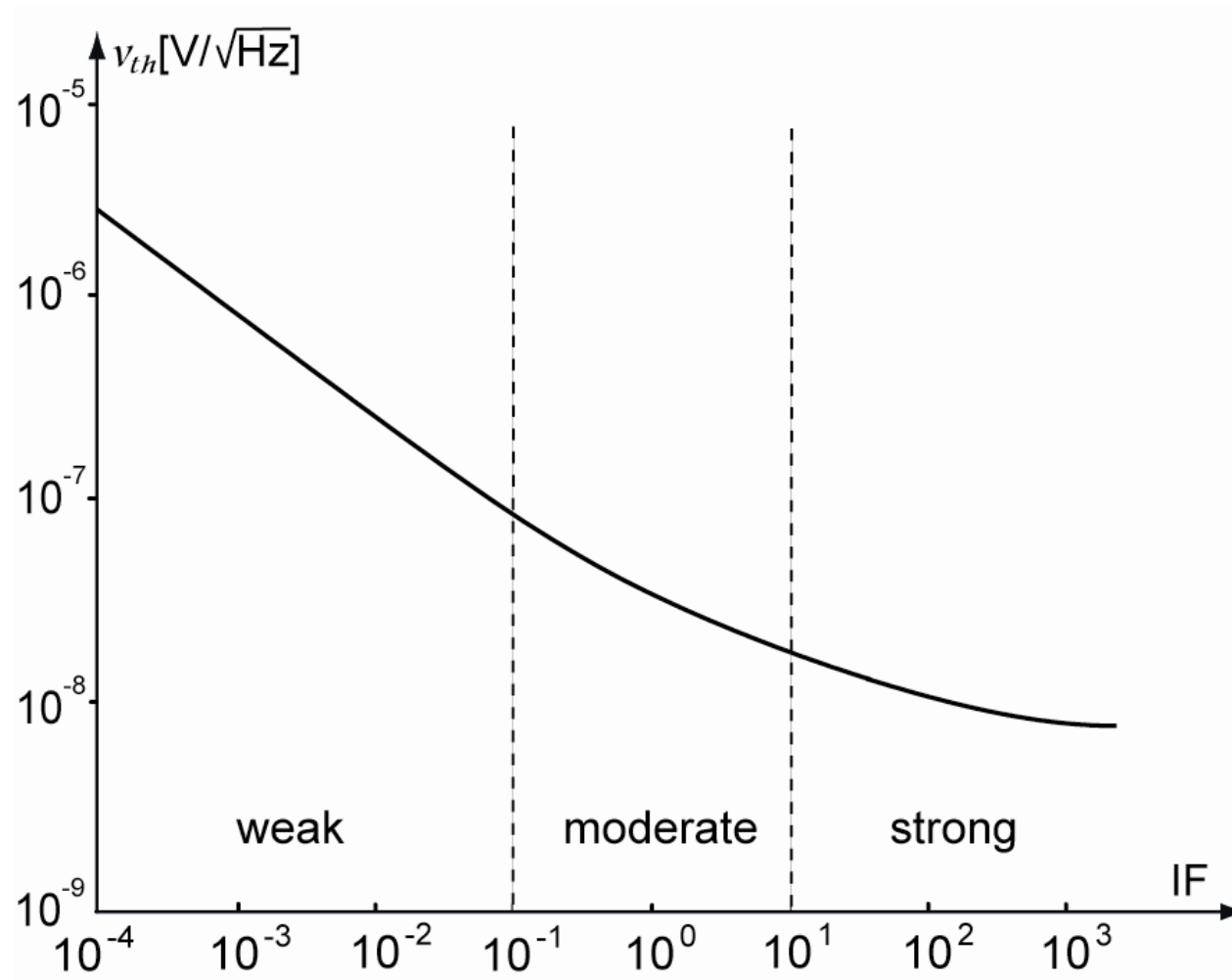
TRANSISTOR LEVEL DESIGN

→ Design parameters vs. variables



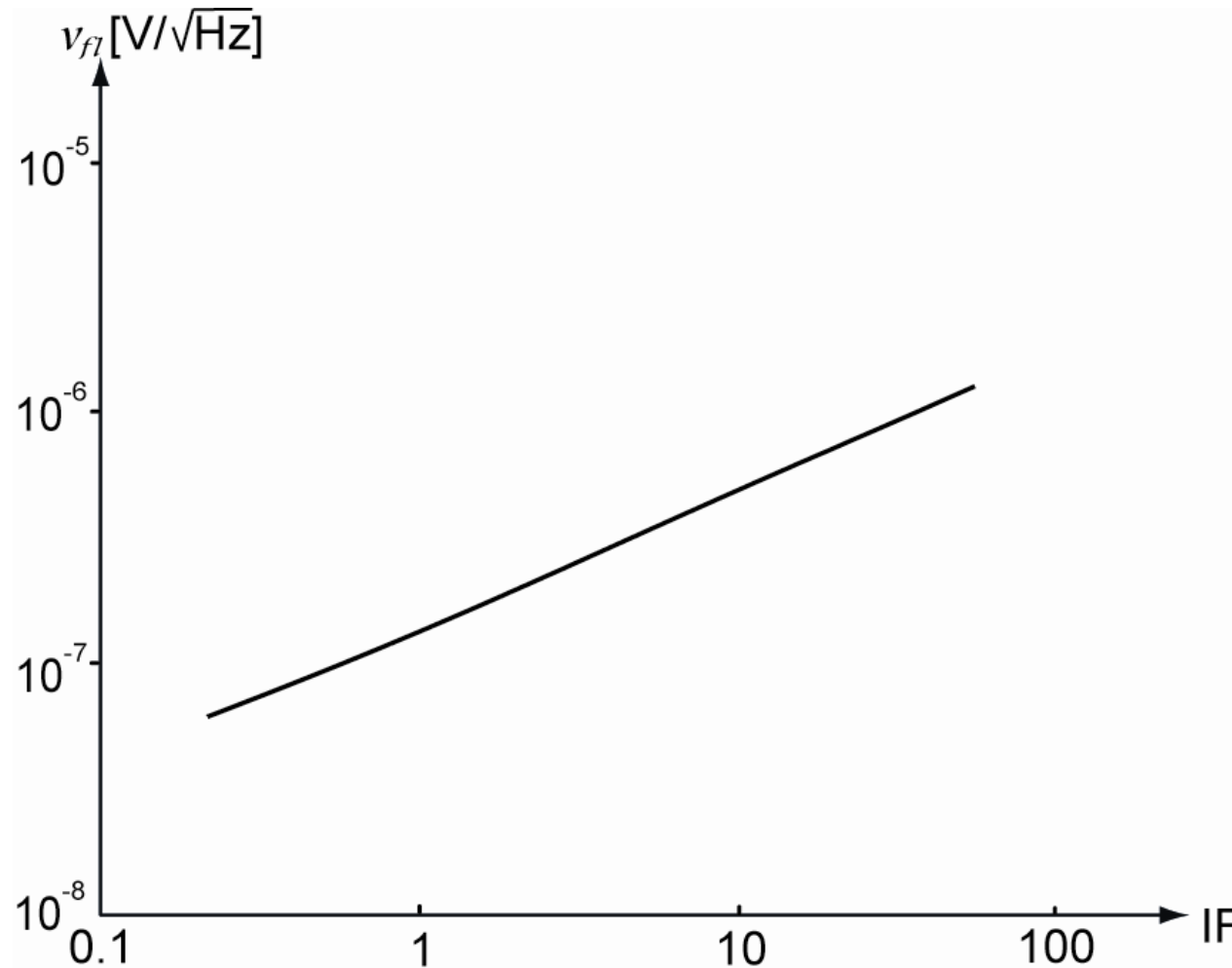
TRANSISTOR LEVEL DESIGN

→ Design parameters vs. variables



TRANSISTOR LEVEL DESIGN

→ Design parameters vs. variables



TRANSISTOR LEVEL DESIGN

→ **Design cases :**

output conductance + saturation voltage

output conductance + transconductance

saturation voltage + gain

gain + sum of par. caps

transconductance + sum of par. caps

transconductance + equiv. noise

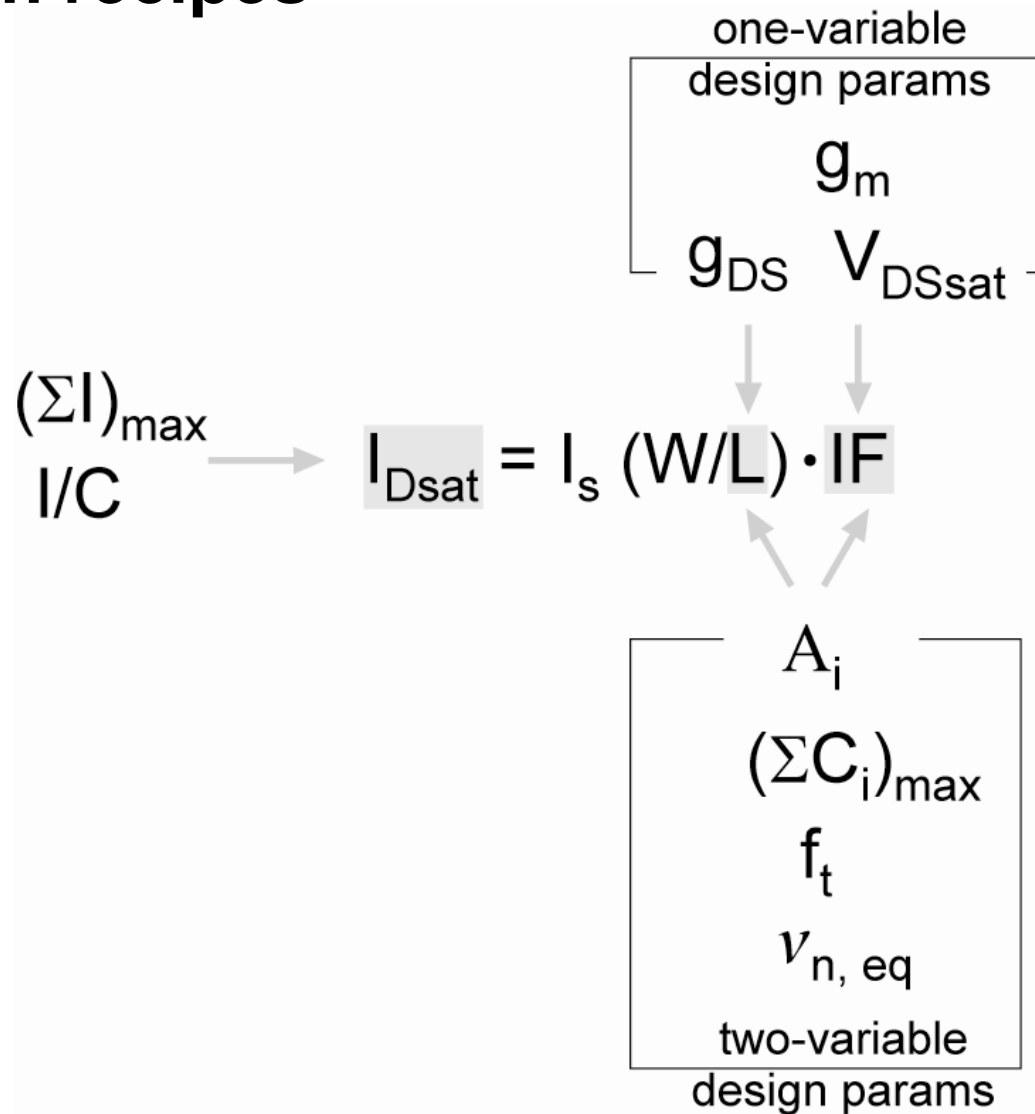
gain + transition frequency

transconductance + voltage mismatch

saturation voltage + current mismatch

TRANSISTOR LEVEL DESIGN

→ Design recipes



DESIGN CHARTS

DC params

Vth: 0.6112 V
 Vd: 1 V
 Vds_sat: 0.1823 V
 Vg: 0.6924 V
 Vb: 0 V
 Vs: 0 V

Small signal params

gm / Id: 13.452 uS / uA
 Early voltage: 371.158 V
 if tef: 0.47197

Physical Dimensions

W: 24.1 um
 L: 10 um
 W/L: 2.41

Operating Point

linear / satur: SAT
 Id: 1.5495 uA
 Idsat: 1.5495 uA

Small Signal Parameters

gm/gds: 73.9673 dB
 rds: 239.53 M
 gm: 20.8452 uS
 gds: 4.17485 nS
 gmbs: 7.54523 uS
 if: 2.3704

Graphs

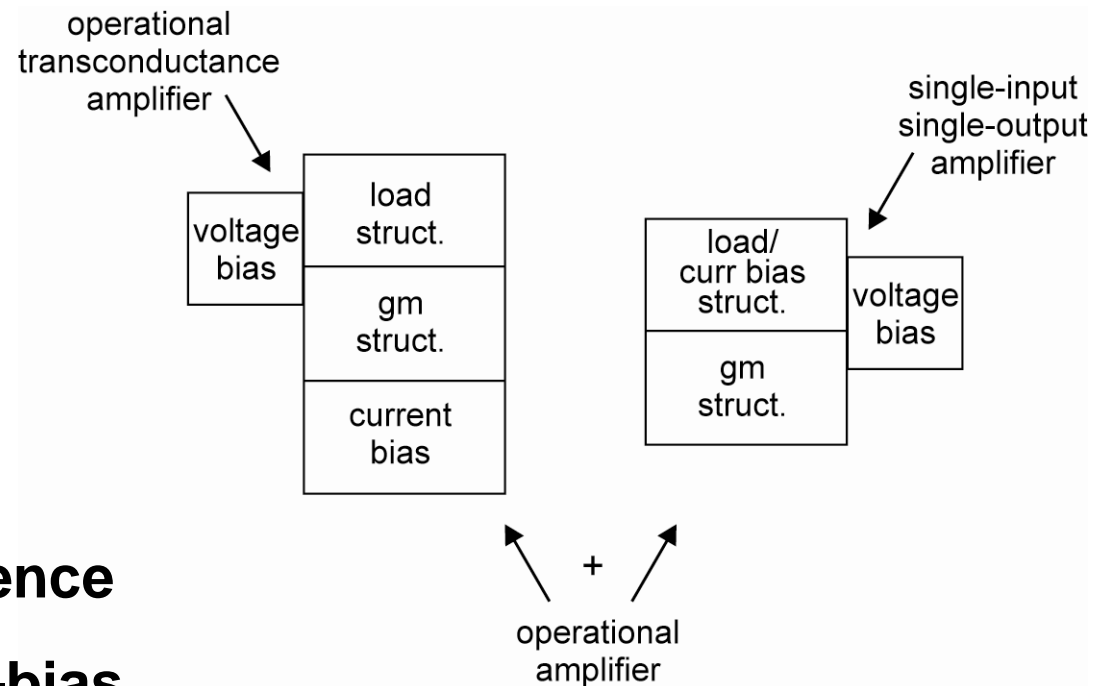
tef: gm vs Id graph showing a red dot at the operating point.

PROCEDURAL DESIGN

→ **Circuit partitioning**

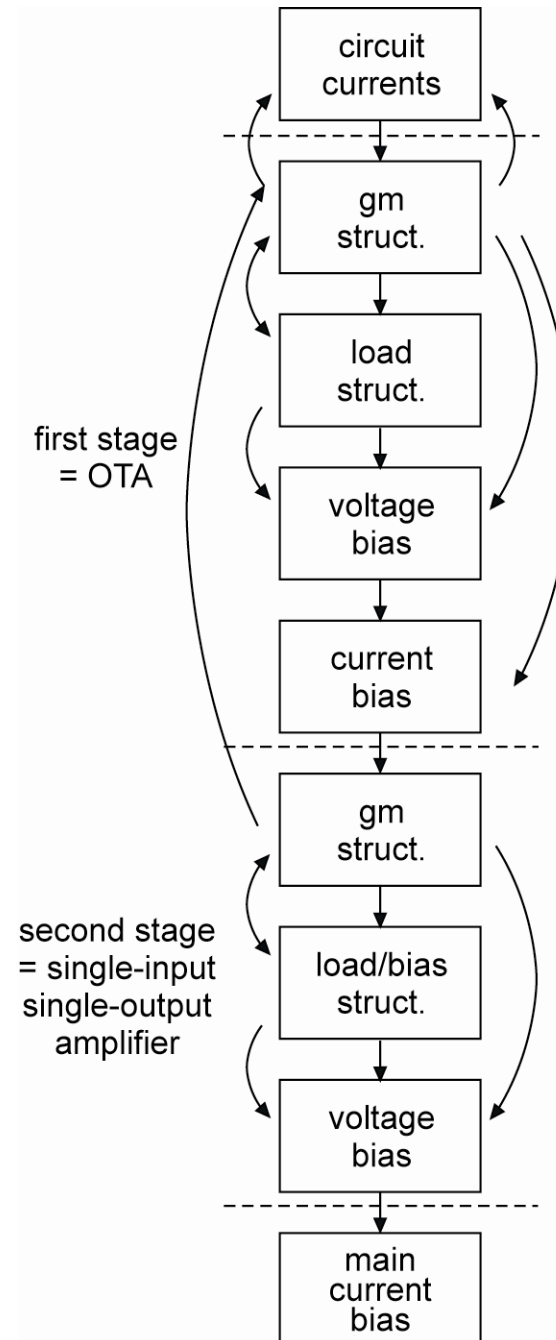
→ **Basic analog structures specifications derivation**

→ **Step-by-step design sequence in transconductance-load-bias structure order**



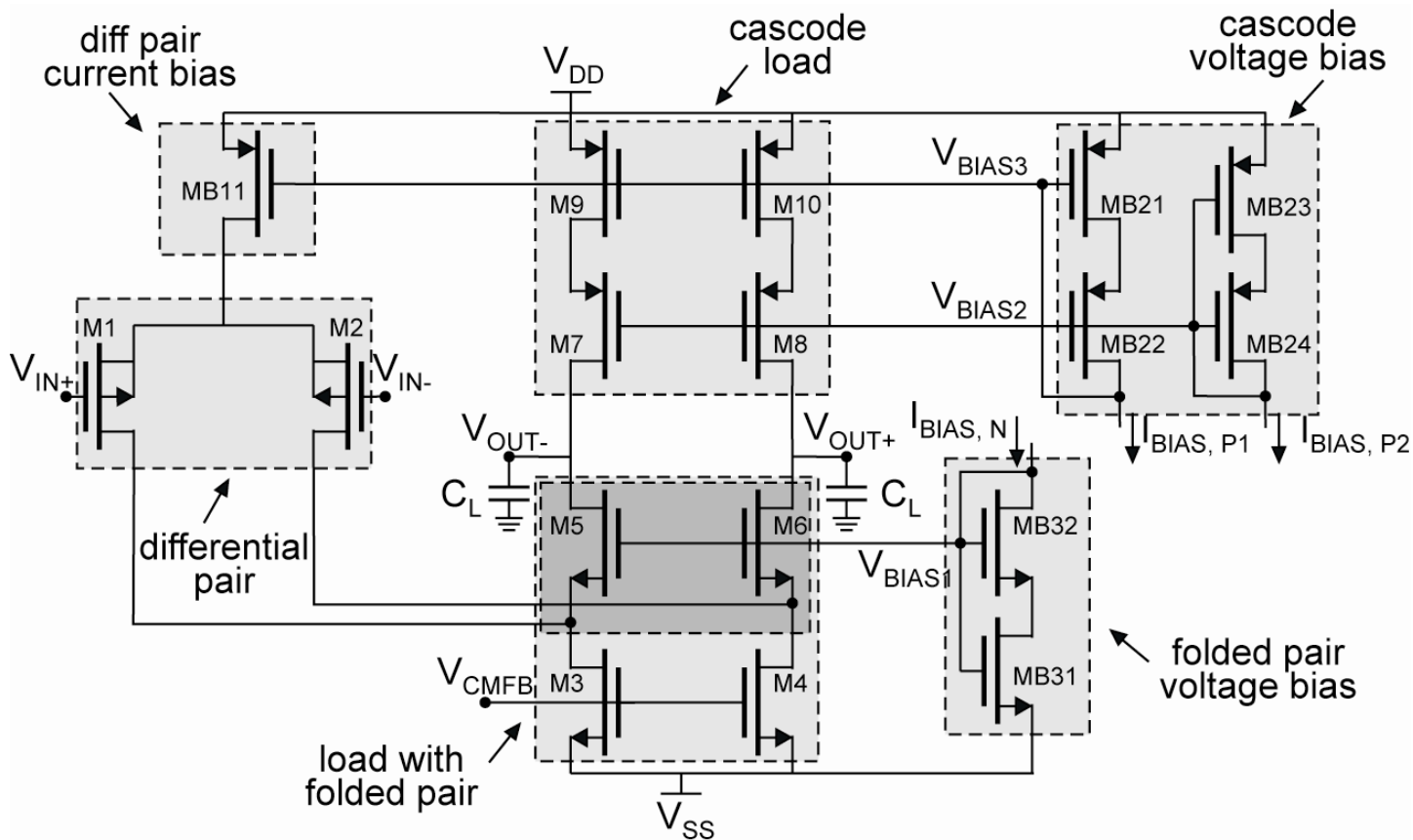
PROCEDURAL DESIGN

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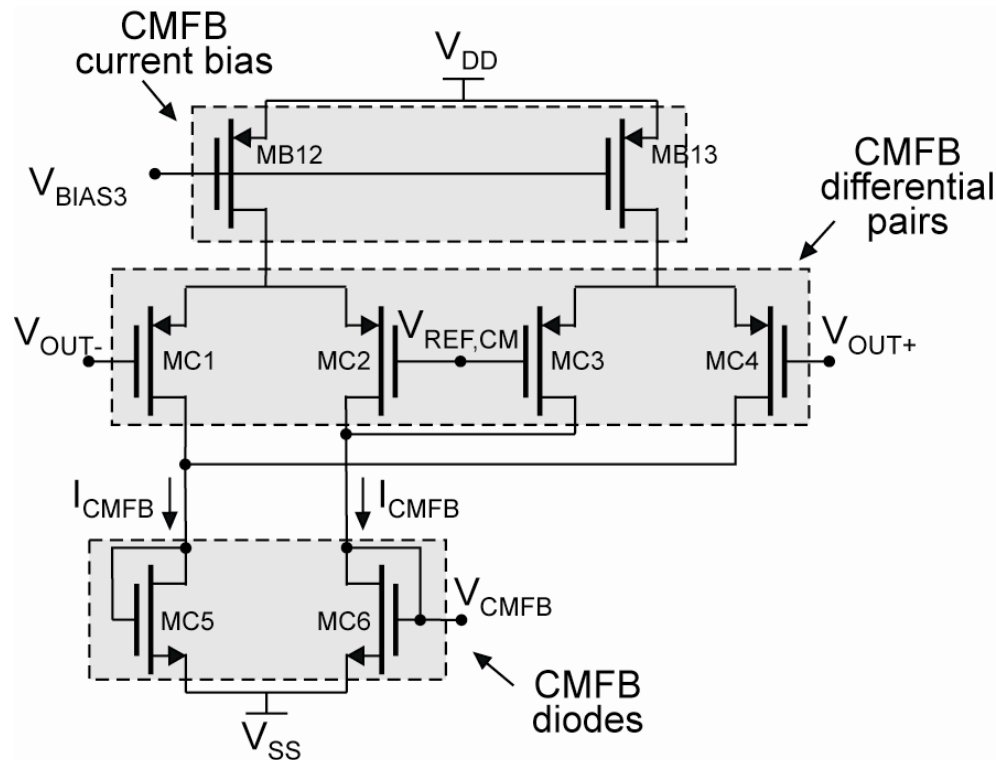
PROCEDURAL DESIGN

→ **Circuit partitioning** → example: fully-differential folded cascode OTA



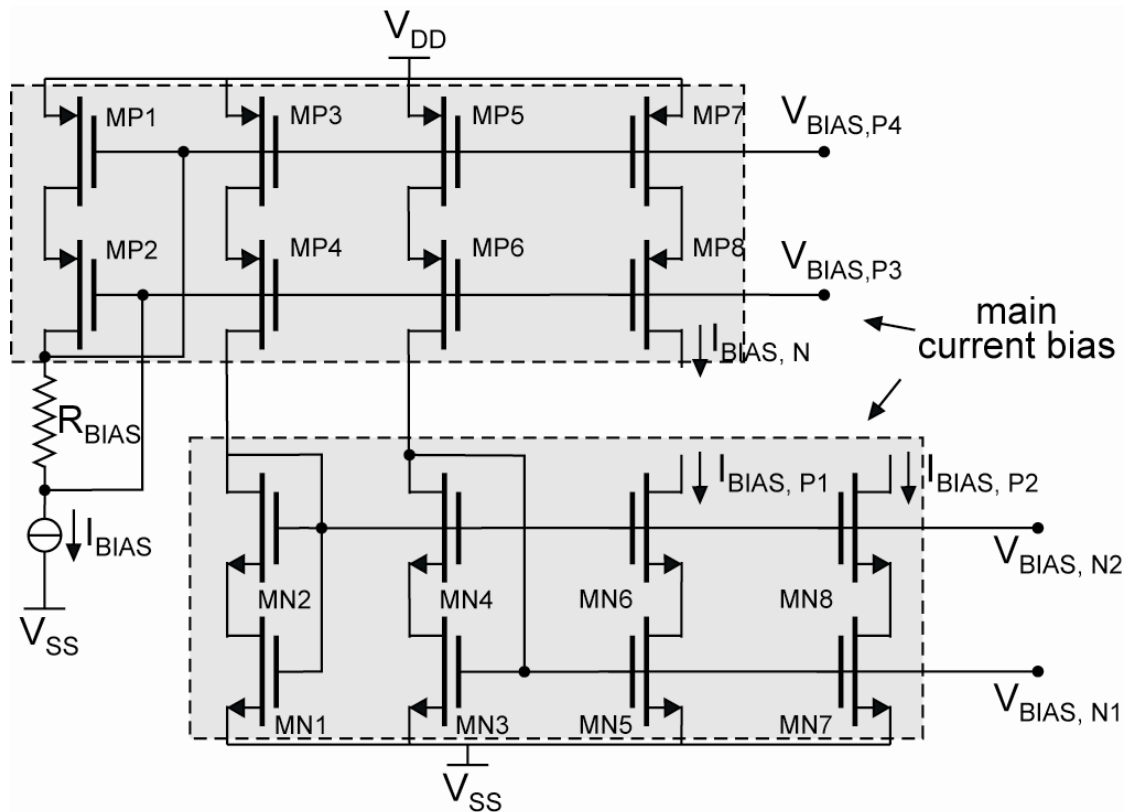
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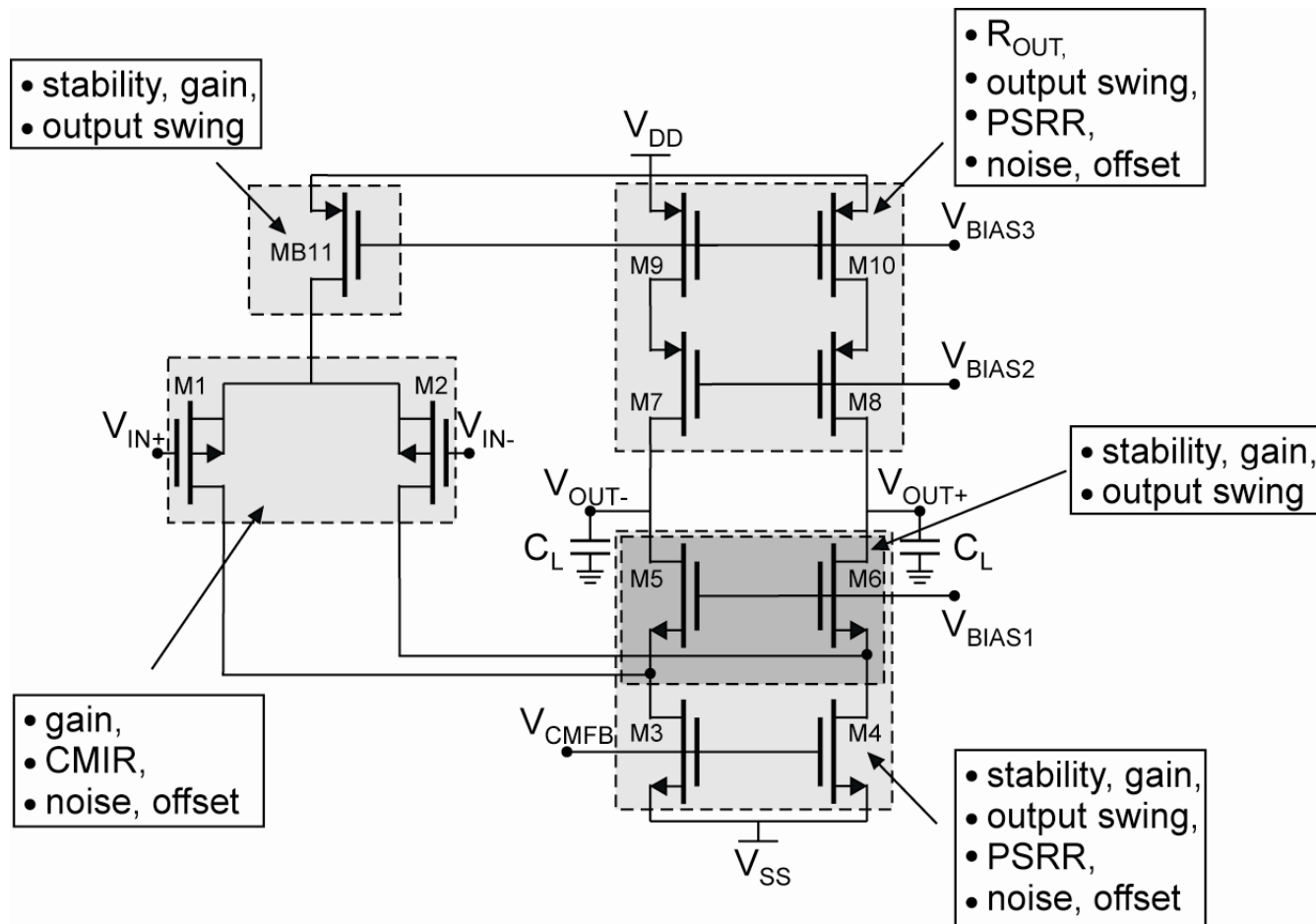
PROCEDURAL DESIGN

→ **Circuit partitioning** → example: fully-differential folded cascode OTA



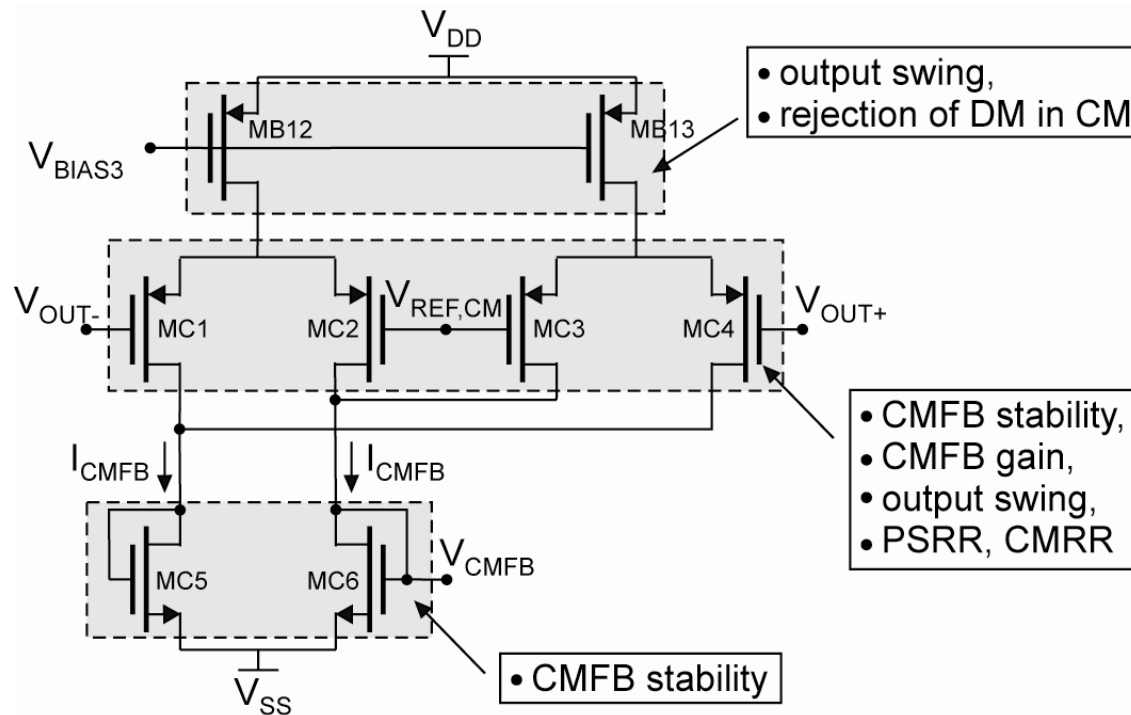
PROCEDURAL DESIGN

→ Specifications derivation → example: fully-differential folded cascode OTA



PROCEDURAL DESIGN

→ Specifications derivation → example: fully-differential folded cascode OTA



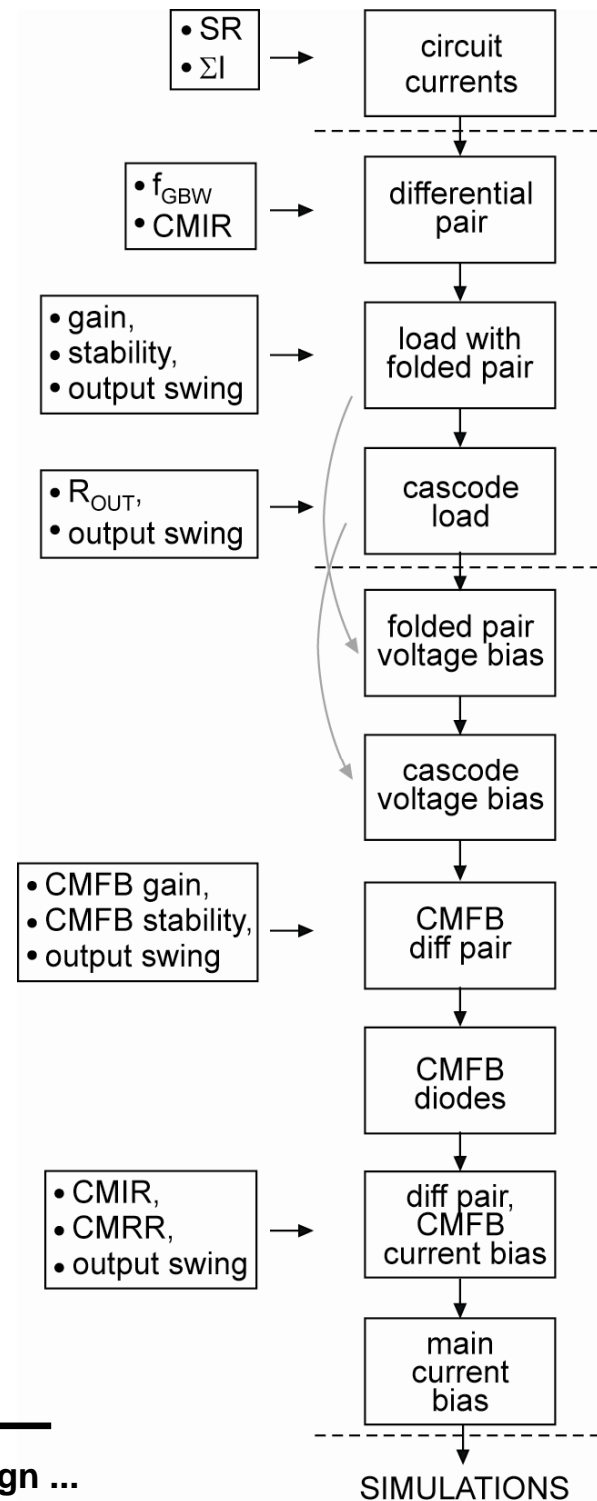
PROCEDURAL DESIGN

→ Design sequence

$$\frac{g_m}{I_{Dsat}} = \frac{1}{nV_t} \cdot \frac{1}{\frac{1}{2} + \sqrt{IF + \frac{1}{4}}}$$

$$V_{DSsat} = V_t \cdot (2\sqrt{IF} + 4)$$

$$g_{DS} = \frac{I_{Dsat}}{L \cdot V_a}$$



PROCEDURAL DESIGN

→ Design optimization

→ Specification propagation

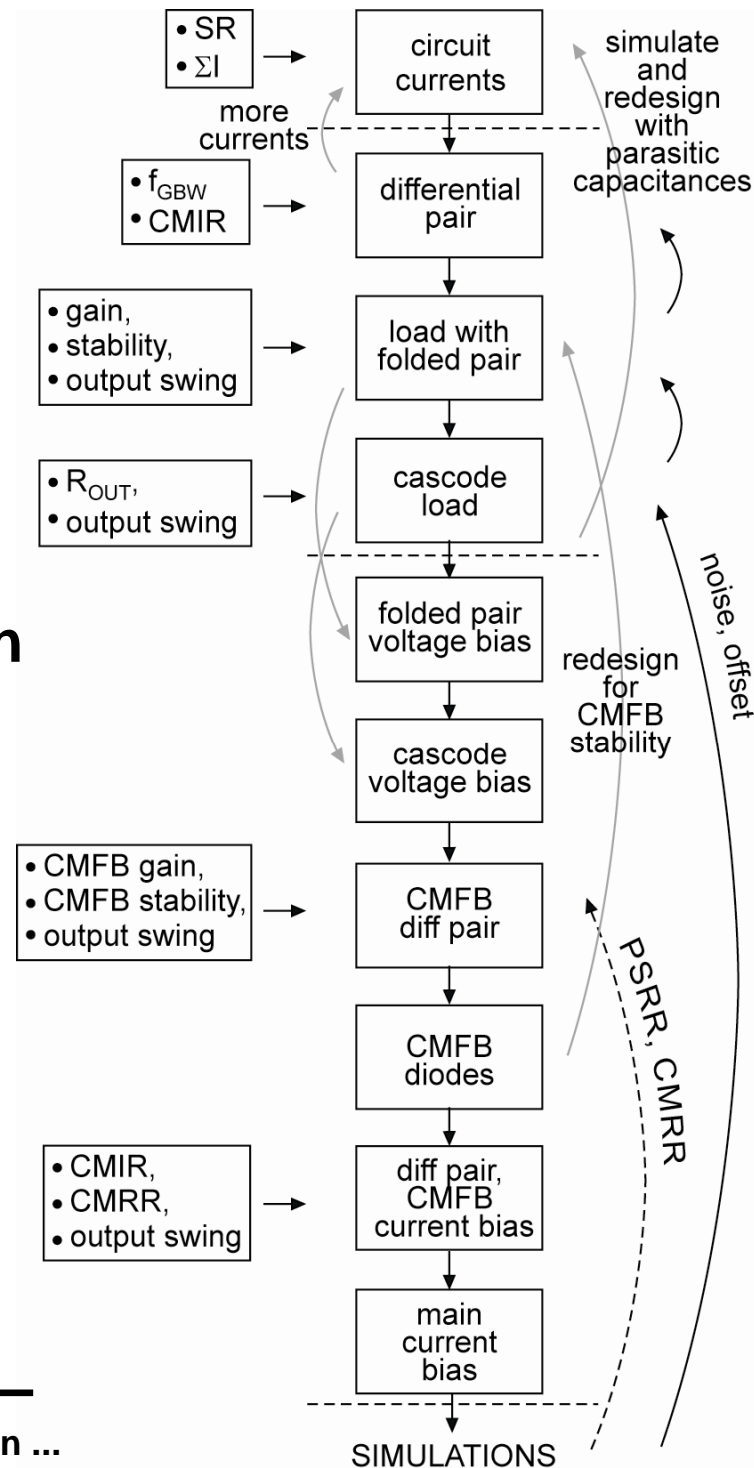
→ Parameters' bounds verification

example:

$$\frac{f_{GBW}}{SR} = \frac{g_m / (2\pi C_L)}{I_{OUT} / C_L} = \frac{g_m}{2\pi I_{OUT}}$$

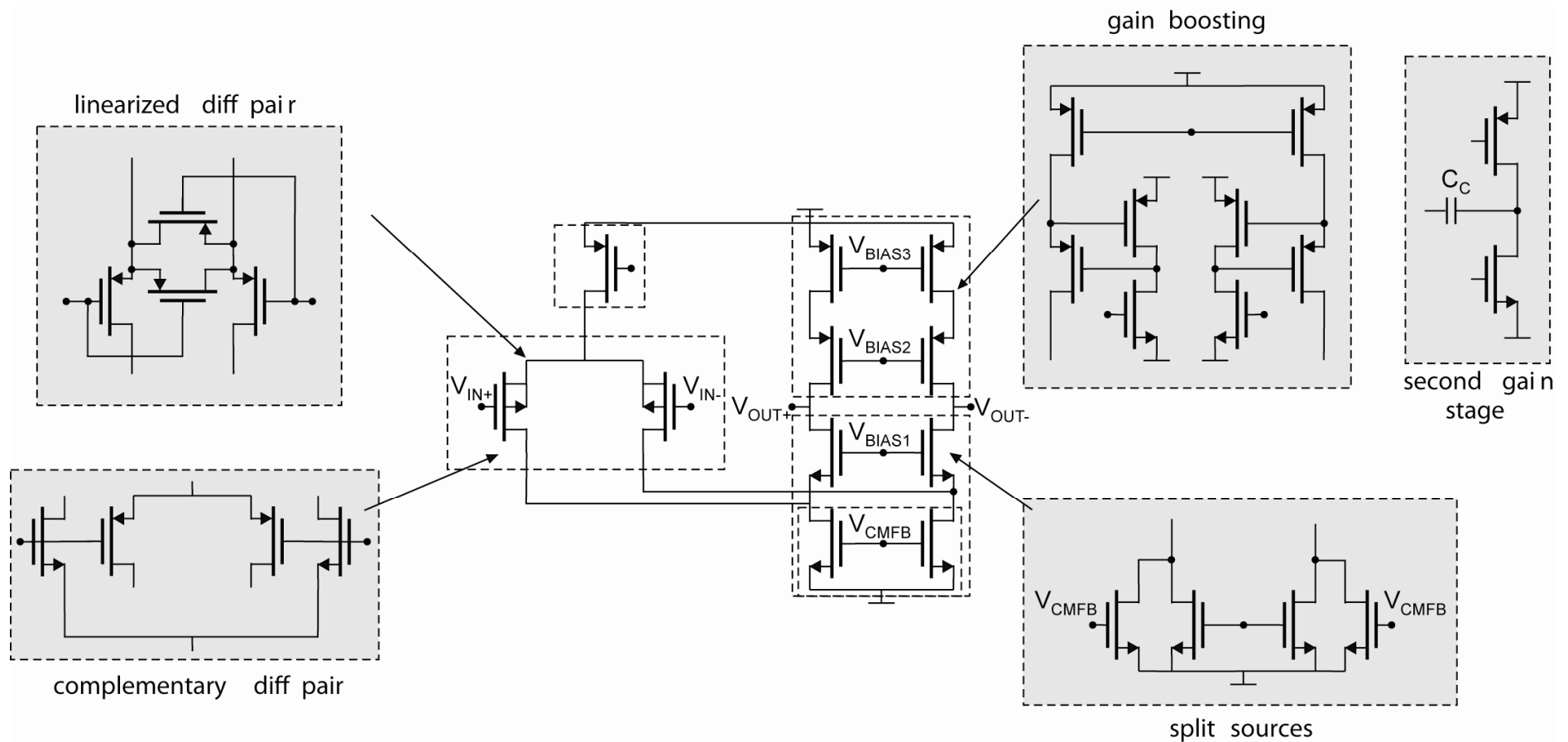
$$= \frac{g_m}{2\pi I_{Dsat}} = \frac{1}{2\pi} \cdot \left(\frac{g_m}{I_{Dsat}} \right)$$

→ Topology variants



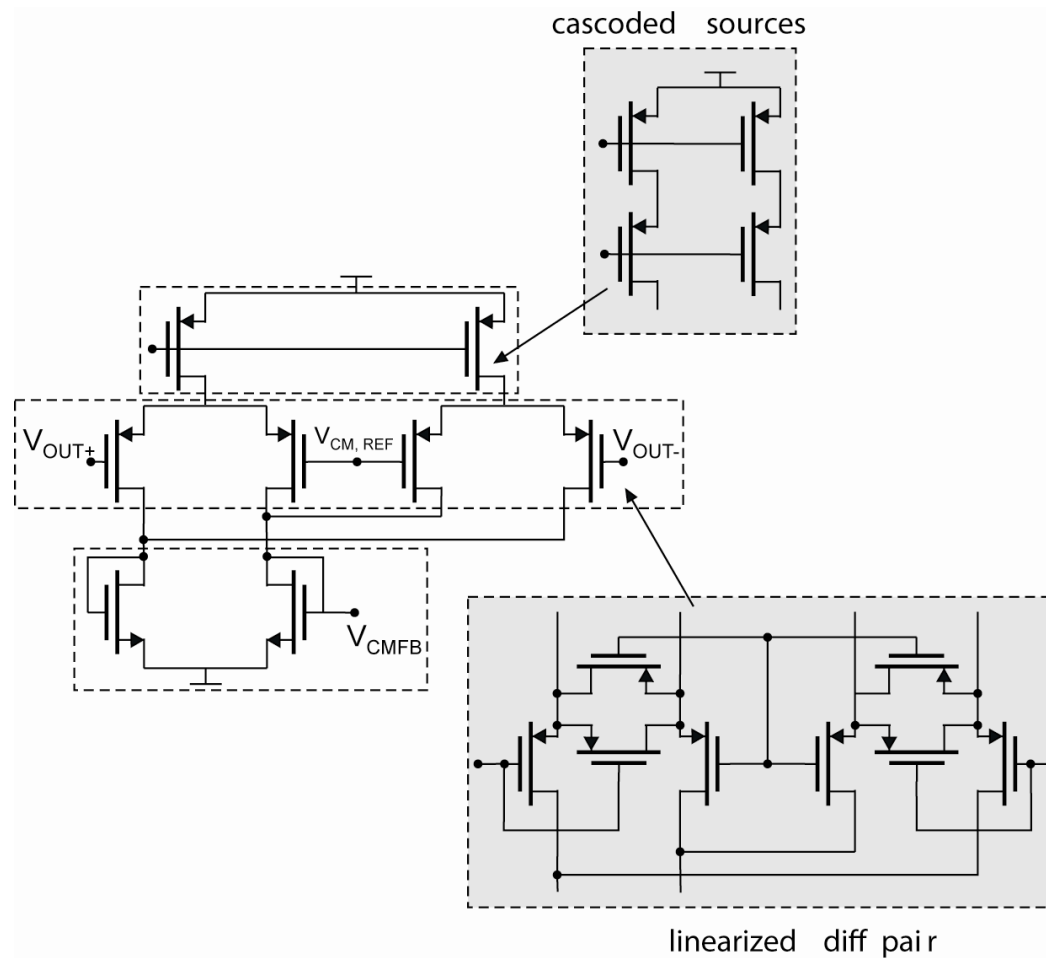
PROCEDURAL DESIGN

→ **Topology variants** → example: fully-differential folded cascode OTA



PROCEDURAL DESIGN

→ **Topology variants** → **example: fully-differential folded cascode OTA**



PAD tool (<http://analog.epfl.ch/>)

→ Basic features

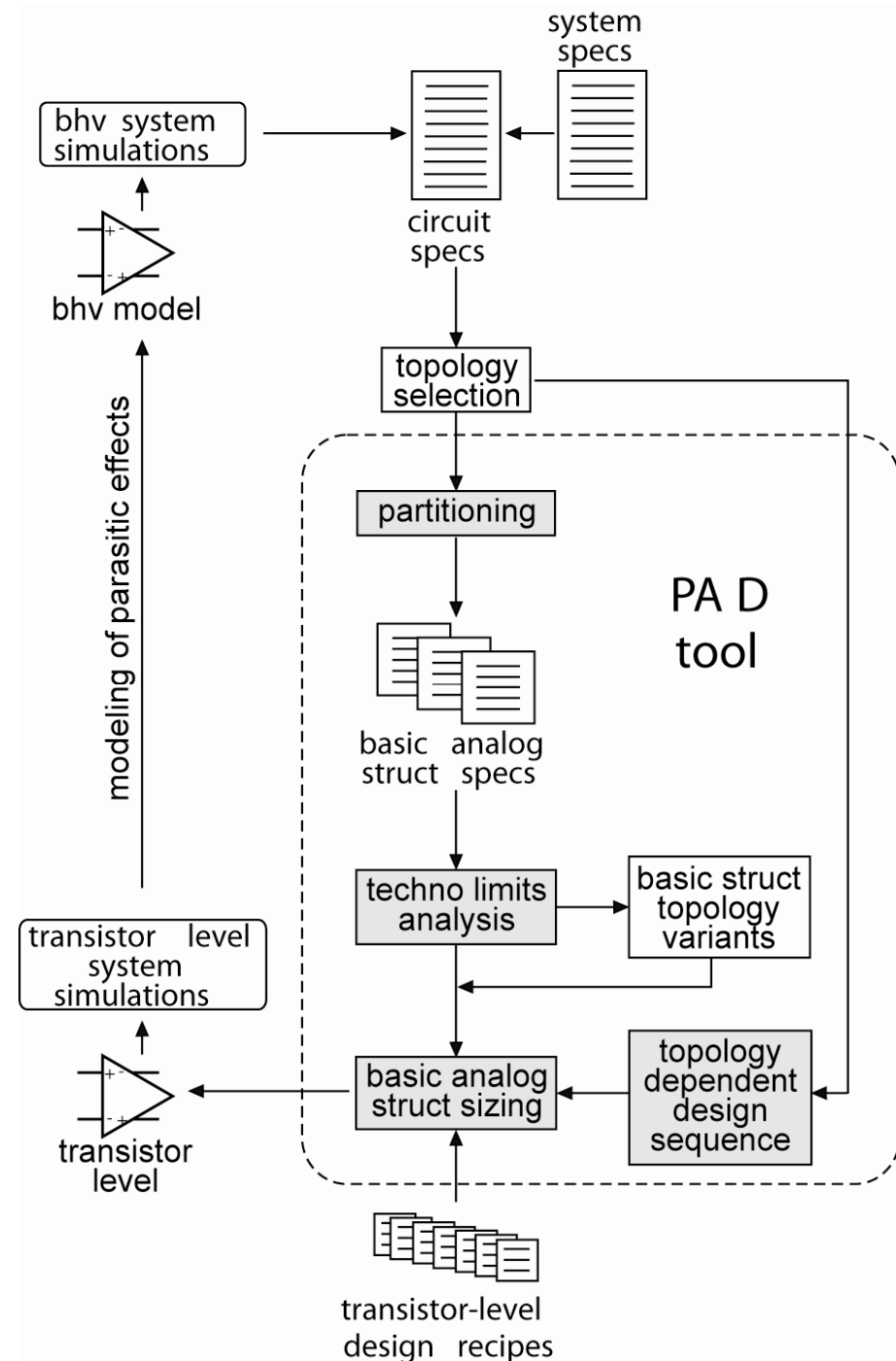
→ Analog design **assistance**

→ **Interactive interface**

→ Step-by-step design
of analog cells

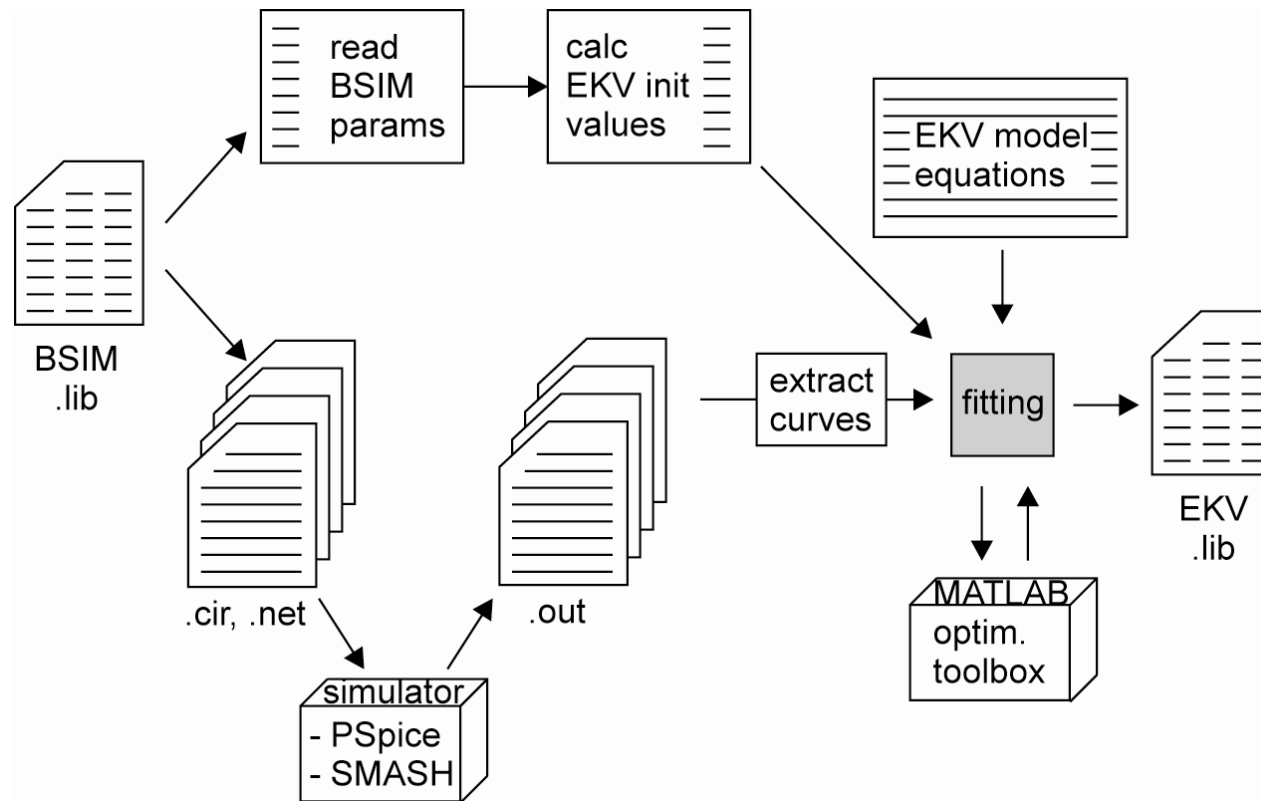
→ **Sizing and optimization**

→ Intuitive understanding



BSIM2EKV tool (<http://analog.epfl.ch/>)

→ Conversion concept



CONCLUSION

- Simplify complex analog design problems by partitioning of analog cells into basic analog structures
- Size each basic analog structure in the environment imposed by the circuit
- Look for the design trade-offs on both circuit level and transistor level
- Use the inversion level as a key design variable

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